

MBE KOMPONENTEN社製 Effusion Cells

Complete range of effusion cells for all kind of deposition



NTEZ

- Suitable for the evaporation of high vapor pressure materials and of organic materials
- Temperature range from 80°C to 400°C / from 300°C to 700°C
- Extremely stable flux rates
- Various crucible sizes and crucible materials
- Various filament configurations



WEZ

- Suitable for the evaporation of most materials evaporated at temperatures up to 1400° C
- Extremely stable flux rates
- Various crucible sizes and crucible materials
- Various filament configurations



HTEZ/HTS

- Suitable for the evaporation of most materials evaporated at temperatures up to 1900° C (2000° C)
- Extremely stable flux rates
- Freestanding tungsten filament (HTEZ)
- High purity pyrolytic graphite (PG) filament (HTS)
- Various crucible sizes and crucible materials



PEZ

- Precise run-to-run flux reproducibility
- Excellent reliability and long lifetime
- Extremely stable flux rates
- Customized beam shaping crucible inserts
- Various crucible sizes and crucible materials
- Various filament configurations



OREZ

- Oxygen resistance option for standard wire heater cells (WEZ, PEZ, NTEZ)
- Ni-alloy-wire heaters up to 1000°C
- Noble-metal-alloy-wire heaters up to 1200°C
- Pressure range from UHV up to several mbar
- Various crucible sizes and crucible materials
- Various filament configurations



OME

- Thermal Conduction Cooling technique (TCC)
- Ideal for evaporation of organic materials and OLED applications
- Temperature range from 15° C up to 350° C
- Optional below room temperature



SUSI

- Growth of thin Si layers
- Si-doping for high mobility GaAs/AlGaAs heterostructures
- Fast and precise flux control
- Ultra high purity silicon filament



SUKO

- Growth of Si-C and Si-Ge-C alloys
- P-type doping in III-V MBE
- Fast and precise flux control
- Ultra high purity pyrolytic graphite (PG) filament



DECO

- Ultra high purity phosphorus (P2) source
- Effusion cell-like operation
- Fast and precise flux control
- Safe and pure doping and growth techniques

薄膜作成に関して、いつでもご相談ください。